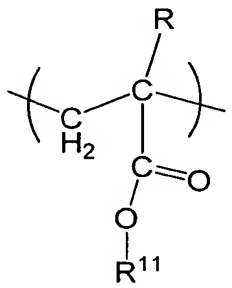
# CLAIMS

1. A resin for a resist, comprising structural units (a) derived from an (α-lower alkyl)acrylate ester as a principal component, wherein

said structural units (a) comprise structural units (a1) derived from an (α-lower alkyl)acrylate ester comprising an acid dissociable, dissolution inhibiting group, and structural units (a2-1) derived from an (α-lower alkyl)acrylate ester comprising a lactone-containing monocyclic group, and

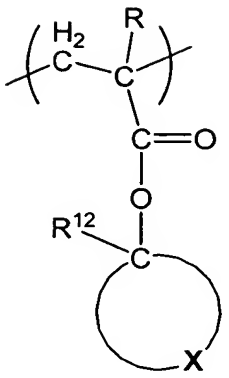
said structural units (a1) comprise structural units (a1-1) derived from an (α-lower alkyl)acrylate ester and represented by a general formula (a1-1) shown below:



(a1-1)

[wherein, R represents a hydrogen atom or a lower alkyl group, and $R^{11}$ represents an acid dissociable, dissolution inhibiting group that comprises a monocyclic aliphatic hydrocarbon group and comprises no polycyclic aliphatic hydrocarbon groups].

2. A resin for a resist according to claim 1, wherein said structural units (a1-1) comprise structural units (a1-2) represented by a general formula (a1-2) shown below:



**(a1-2)**

[wherein, R represents a hydrogen atom or a lower alkyl group, $R^{12}$ represents a lower alkyl group, and X represents a group which, in combination with a carbon atom to which said group $R^{12}$ is bonded, forms a monocyclic aliphatic hydrocarbon group].

3. A resin for a resist according to claim 1, wherein said structural units (a) also comprise structural units (a3) derived from an (α-lower alkyl)acrylate ester that comprises a polar group-containing aliphatic hydrocarbon group.

4. A resin for a resist according to claim 1, wherein said structural units (a) also comprise other structural units (a4) derived from an (α-lower alkyl)acrylate ester that comprises a polycyclic aliphatic hydrocarbon group, which differ from said structural units (a2) and (a3).

5. A positive resist composition comprising: (A) a resist resin component that exhibits increased alkali solubility under action of acid, and (B) an acid generator component that generates acid on exposure, wherein

said component (A) comprises a resin for a resist according to claim 1.

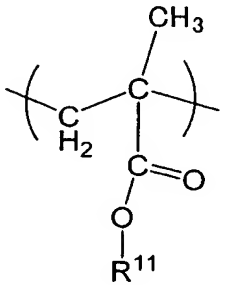
6. A positive resist composition according to claim 5, further comprising a nitrogen-containing organic compound.

7. A method of forming a resist pattern, comprising the steps of: forming a positive resist film on top of a substrate using a positive resist composition according to claim 5, conducting a selective exposure treatment of said positive resist film, and performing alkali developing to form a resist pattern.

8. A resin for a resist, comprising structural units (a) derived from an (α-lower alkyl)acrylate ester as a principal component, wherein

said structural units (a) comprise structural units (a1) derived from an (α-lower alkyl)acrylate ester comprising an acid dissociable, dissolution inhibiting group, and structural units (a2) derived from an (α-lower alkyl)acrylate ester comprising a lactone-containing monocyclic or polycyclic group, and

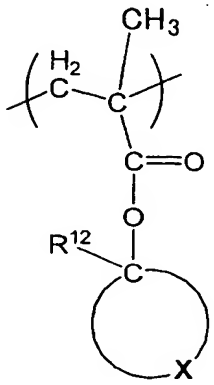
said structural units (a1) comprise structural units (a1-1-1) derived from a methacrylate ester and represented by a general formula (a1-1-1) shown below:



(a1-1-1)

[wherein, $R^{11}$ represents an acid dissociable, dissolution inhibiting group that comprises a monocyclic aliphatic hydrocarbon group and comprises no polycyclic aliphatic hydrocarbon groups].

9. A resin for a resist according to claim 8, wherein said structural units (a1-1-1) comprise structural units (a1-2-1) represented by a general formula (a1-2-1) shown below:



(a1−2−1)

[wherein, $R^{12}$ represents a lower alkyl group, and X represents a group which, in combination with a carbon atom to which said group $R^{12}$ is bonded, forms a monocyclic aliphatic hydrocarbon group].

10. A resin for a resist according to claim 8, wherein said structural units (a) also comprise structural units (a3) derived from an (α-lower alkyl)acrylate ester that comprises a polar group-containing aliphatic hydrocarbon group.

11. A resin for a resist according to claim 8, wherein said structural units (a) also comprise other structural units (a4) derived from an (α-lower alkyl)acrylate ester that comprises a polycyclic aliphatic hydrocarbon group, which differ from said structural units (a2) and (a3).

12. A positive resist composition comprising: (A) a resist resin component that exhibits increased alkali solubility under action of acid, and (B) an acid generator component that generates acid on exposure, wherein

said component (A) comprises a resin for a resist according to claim 8.

13. A positive resist composition according to claim 12, further comprising a nitrogen-containing organic compound.

14. A method of forming a resist pattern, comprising the steps of: forming a positive resist film on top of a substrate using a positive resist composition according to claim 12, conducting a selective exposure treatment of said positive resist film, and performing alkali developing to form a resist pattern.